

ABSTRACT

A method of etching an alloy of aluminum and neodymium by exposing the alloy to a plasma formed from a gas mixture of chlorine and hydrogen iodide (HI). The hydrogen iodide etches the neodymium component of the alloy, and the chlorine etches the aluminum component. Preferably, the gas mixture further includes BCl_3 to provide sputter etching by boron ions.

This Sheet Has Been Replaced

